Press Release



Rigaku Innovative Technologies Features Latest Synchrotron Optics and Coating Capabilities at SRI 2018

Rigaku Innovative Technologies Nick Grupido Vice President, Sales & Marketing tel: +1 248-232-6400 x6441 Nick,Grupido@rigaku.com

Rigaku Innovative Technologies (RIT) is presenting its high-performance multilayer optics and advanced coatings services at the 13th International Conference on Synchrotron Radiation Instrumentation

June 10, 2018 – Taipei, Taiwan. Rigaku Innovative Technologies (<u>RIT</u>) is pleased to announce its attendance at the 13th International Conference on Synchrotron Radiation Instrumentation (<u>SRI 2018</u>). RIT, the components division of <u>Rigaku Corporation</u> and manufactures <u>Osmic® optics</u>, the most widely used brand of multilayers and X-ray source systems in the world, will be presenting its line of high-performance multilayer optics at booth 3SH2.

The conference is hosted by the National Synchrotron Radiation Research Center (<u>NSRRC</u>) and takes place from June 10 to 15, 2018 at the <u>Taipei International Convention</u> <u>Center</u> in Taipei, Taiwan. A 5-day scientific program will feature invited and contributed oral presentations in plenary and parallel sessions, poster and exhibition sessions, and a tour to the recently opened 3-GeV facility, Taiwan Photon Source (<u>TPS</u>) at NSRRC.

RIT offers single film, multilayer and crystal optics for synchrotron beamlines and endstations. RIT also cleans and recoats old optics to either repurpose the optic for a new application or to refurbish or repair the coatings to get enhanced performance.

Synchrotron beamline end stations and analytical instruments most often operate with high-intensity X-rays. Such high-intensity beams can damage single film and multilayer coatings. RIT has developed a proprietary methodology for the complete refurbishment, recovery and restoration of synchrotron and custom multilayer systems.

RIT produces high-reflectivity and high-precision coatings on mirrors up to 1.3 meters long, with the ability to coat double multilayer monochromators optics up to 1.5 meters in length. Enabled by RIT's ability and experience with coating multiple stripes with different material systems, coatings can be single film, bi-material or tri-material multilayers and made in narrow stripes to allow multiple material systems to be coated on the same optic, with a coating uniformity of 0.5% over a length of 1 meter. Substrates can be flat or figured into virtually any practical shape.



For additional information about RIT and its EUV related products, please visit:

www.rigaku.com/products/optics/euv

www.rigakuoptics.com

About RIT

RIT is at the forefront of multilayer optic technology for EUV lithography. Formerly Osmic Inc., RIT was the first commercial supplier of multilayer optics for X-ray sciences. Since 1993, RIT has been a global leader in the development and supply of EUV optics, thus shaping the vision of EUVL for high-volume manufacturing. With hundreds of major innovations to its credit, Rigaku and its subsidiary companies are world leaders in the fields of small molecule and protein crystallography, X-ray spectrometry and diffraction, X-ray optics, as well as semiconductor metrology. Rigaku employs over 1,400 people globally and its products are in use in more than 90 countries – supporting research, development, production control and quality assurance activities. Throughout the world, Rigaku continuously promotes partnerships, dialog, and innovation within the global scientific and industrial community.

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